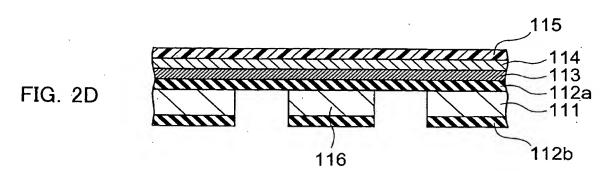
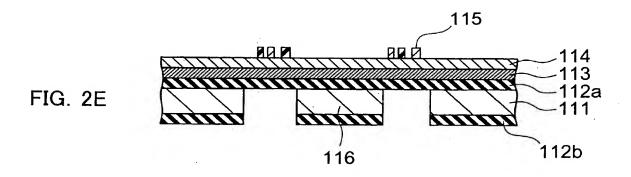


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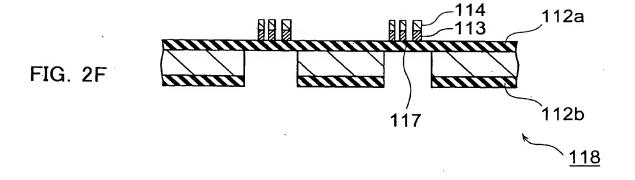
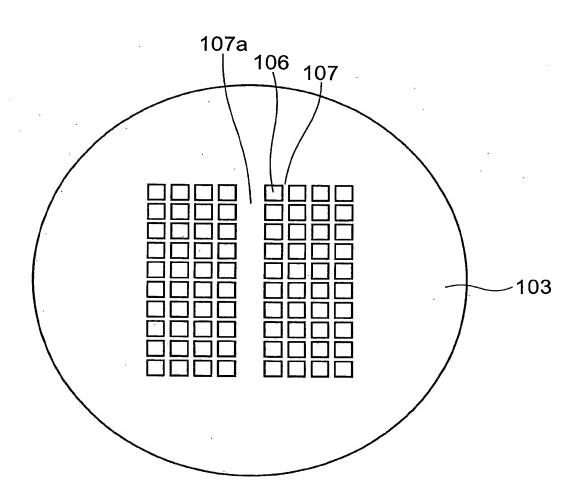


FIG. 3



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FIG. 4

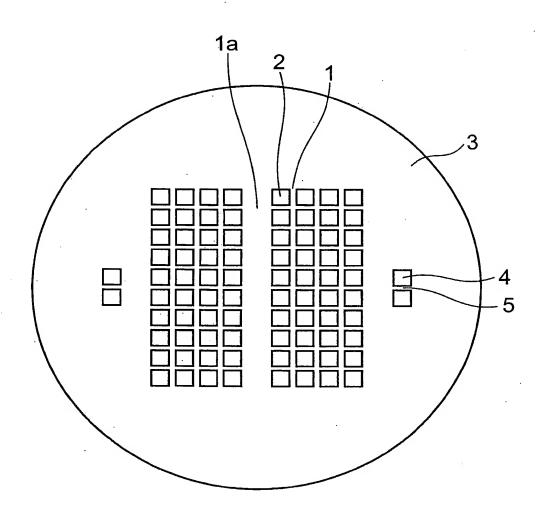
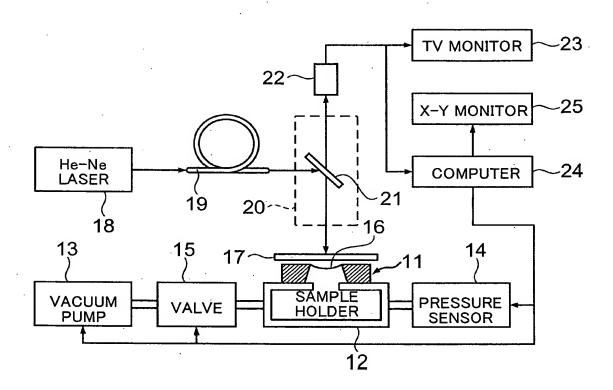


FIG. 5



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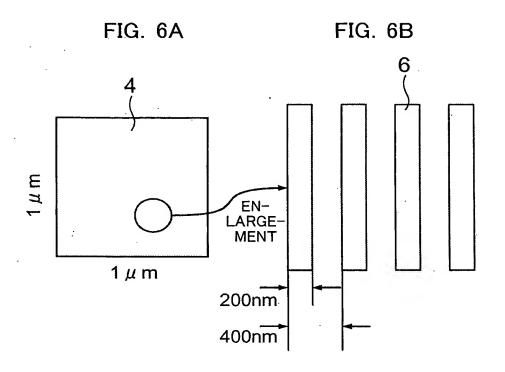
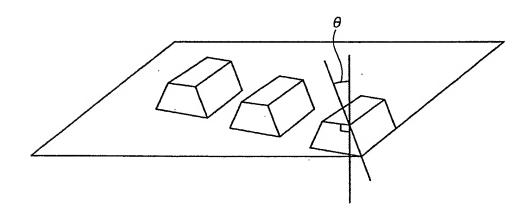
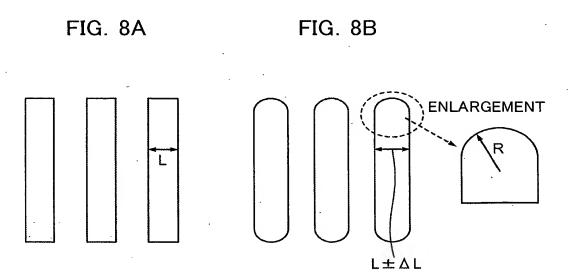
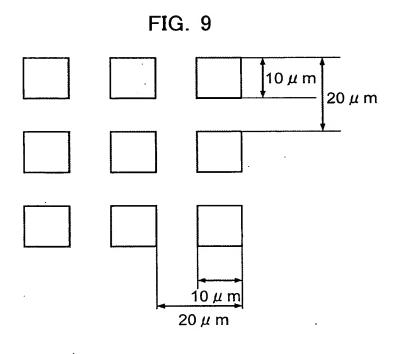


FIG. 7





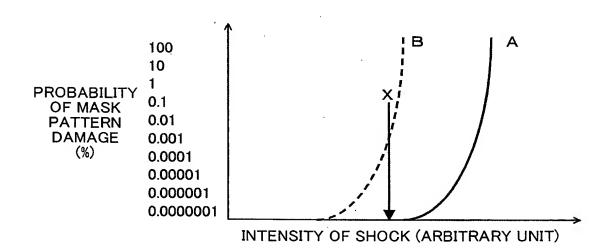


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FIG. 10A FIG. 10B

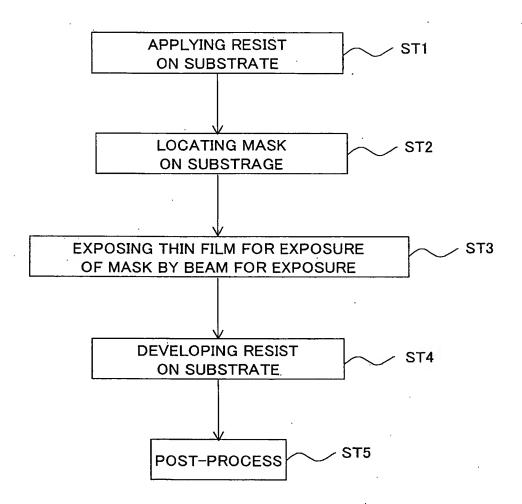
FIG. 11



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FIG. 12.



## LIST OF REFERENCE

	1, 1a	beam
	2	membrane
5	3	silicon wafer
. •	4	membrane for inspection
	5	beam
	6	line-and-space pattern
	11	mask
10	12	sample holder
•	13	vacuum pump
	14	pressure sensor
	15	valve
	16	membrane
15	17	optical glass
	18	He-Ne laser
	19	single-mode fiber optic
	20	microscope
	21	half mirror
20	22	CCD camera
	23	TV monitor
	24	computer
	25	X-Y monitor
	101	SOI wafer
25	102	silicon oxide film

## MASK, METHOD OF INSPECTING THE SAME, AND METHOD OF PRODUCING SEMICONDUCTOR DEVICE Inventor: Yoko Watanabe et al. Attorney Docket No.: 075834.00404 Robert J. Depke, Holland & Knight LLC - (312) 263-3600

silicon wafer

		orradoi: warer
	104	silicon oxide film
	105	silicon layer
٠	106	membrane
5	107, 107a	beam
	108	resist
	109	hole
	110	stencil mask
	111	silicon wafer
.10	112a, 112b	silicon nitride
	113	chromium layer
	114	tungsten layer
	115	resist
	116	beam
15	117	membrane
	118	scattering membrane mask

103...